

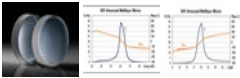
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25.4mm Dia. x 250mm EFL, 19nm (65eV), 5° EUV/XUV Attosecond Multilayer Concave Mirror

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UltraFast Innovations (UFI) EUV/XUV Attosecond Multilayer Mirrors



Stock **#16-766** 2 In Stock

-

1

+

S\$3,528⁰⁰

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Qty 1+	S\$3,528.00 each
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General	
Concave Mirror	Type:
330 attoseconds	Supported Pulse Duration:
Model Number:	

XUV65BW6	
Physical & Mechanical Properties	
25.40 ±0.13	Diameter (mm):
Commercial Polish	Back Surface:
80	Clear Aperture (%):
Fine Ground	Edges:
<1	Surface Roughness (□):
6.35 ±0.20	Edge Thickness ET (mm):

Optical Properties	
Fused Silica (Corning 7980)	Substrate: □
Rs > 38% @ 65eV/19nm	Coating Specification:
EUV Multilayer (19nm)	Coating:
5	Angle of Incidence (°):
19	Design Wavelength DWL (nm):
250.00	Effective Focal Length EFL (mm):
500.00	Radius of Curvature (mm):
500.00	Radius R ₁ (mm):
λ/10	Irregularity (P-V) @ 632.8nm:
>38	Reflection at DWL (%):

Electrical	
65 ±2	Center Energy (eV):
6	Bandwidth (eV):

Regulatory Compliance	
Compliant	RoHS 2015:
View	Certificate of Conformance:
Compliant	Reach 235:

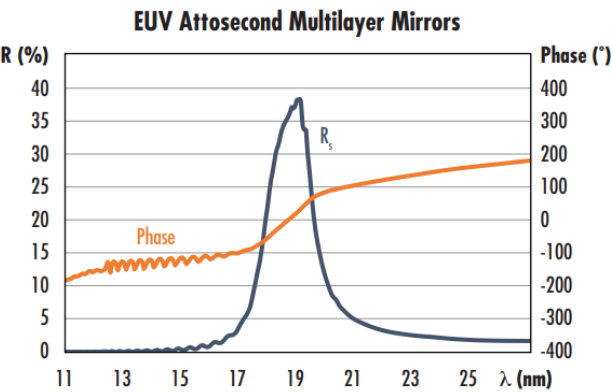
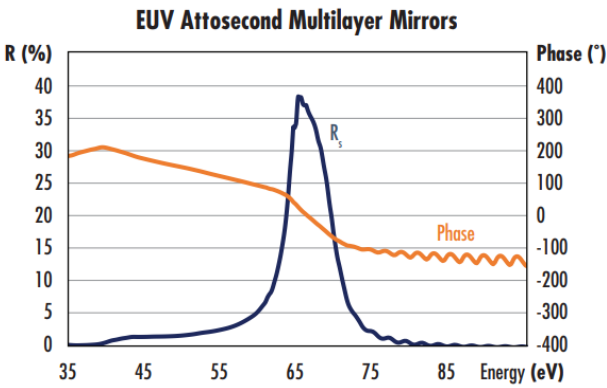
Product Details

- Designed for 330 Attosecond Pulses @65eV (19nm)
- Multilayer Coating with 38% Peak Reflectivity
- ≤1Å(Angstrom) Surface Roughness Superpolished Substrates
- EUV Flat Mirrors and EUV Spherical Mirrors Designed at 13.5nm Also Available
- No Minimum Order Quantities, No Coating Lot Charges
- Platinum-Level 2022 Laser Focus World (LFW) Innovators Award

UltraFast Innovations (UFI) Extreme Ultraviolet (EUV/XUV) Attosecond Multilayer Mirrors are designed for steering, focusing, and shaping attosecond pulses. Their multilayer coating is centered at 65eV (19nm) with a 6eV (1.8nm) bandwidth and provides a peak reflectivity of 38% for s-polarized light. These mirrors support EUV pulses with a temporal duration of 330 attoseconds. UFI Extreme Ultraviolet (EUV/XUV) Attosecond Mirrors are ideal for attosecond pulse generation and shaping based on high harmonic generation (HHG), free electron lasers (FELs), or other quantum optical applications.

Atomic precision ion beam deposition results in atomically-smooth coating layers. These mirrors allow for precision control of wavelength and spectral phase with high efficiency in a growing application space. Attosecond science pushes the limits of ultrafast lasers, providing access to some of the most fundamental scientific processes like the motion of electrons. EUV Mirrors are also known as XUV/Soft X-Ray Mirrors. The physical principal behind EUV Attosecond Multilayer Mirrors is the interference of reflected and scattered EUV radiation from each interface of the multilayer stack. Flat and concave mirrors with a 25.4mm diameter are available; please contact us if your application requires an EUV multilayer mirror with a customized center energy, bandwidth, or other specifications.

Technical Information



Special Handling

These optics require special handling to avoid damage and ensure long-term performance. Proper handling, cleaning, and storage are essential to maintain optical quality. Explore our [Optics Cleaning Resources](#) for step-by-step guides and best practices. For personalized assistance, [Email us](#) or [Chat](#) with our technical support team.



Component Handling Tools

Compatible Mounts